



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
HONGO *et al.*

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Confirmation No. 4649

Application No.: 09/815,305

NOV 07 2002

TC 1700

Filed: March 23, 2001

ART UNIT: 1763

Title: PLASMA PROCESSING APPARATUS
HAVING AN EVACUATING ARRANGEMENT TO
EVACUATE GAS FROM A GAS-INTRODUCING
PART OF A PROCESS CHAMBER

Examiner: ALEJANDRO MULERO, L.

#8A
11/7/02
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November 6, 2002

AMENDMENT

Hon. Commissioner of Patents
Washington, DC 20231

Sir:

Responsive to the Office Action dated August 13, 2002, please amend the above
identified application as follows:

IN THE CLAIMS

Please cancel claims 2 and 3 without prejudice or disclaimer

Please amend claims 1 and 7 as follows:

1. (Amended) A plasma processing apparatus for applying a plasma process to an object
to be processed, the plasma processing apparatus comprising:

A
a process chamber in which the object to be processed is subjected to the plasma
process;

a gas-introducing part connected to said process chamber so as to introduce a reactant
gas into said process chamber;

a first vacuum pump connected to said process chamber so as to evacuate gas from
said process chamber so that said process chamber is maintained at a negative pressure; and